

Kindly cancel all the claims and add the following claims 1-24:

In the claims:

1. A polishing tool for polishing silicon wafers, said tool comprising an endless belt which includes a continuous unseamed textile fabric supporting a polishing layer, said polishing layer comprising a microcellular or microporous urethane.
2. A polishing tool according to claim 1 wherein said fabric is woven and comprises aramid yarns oriented in the lengthwise direction.
3. A polishing tool according to claim 2 wherein said polishing layer comprises two layers which are of different hardnesses.
4. A polishing tool according to claim 1 wherein an exposed surface of said polishing layer is formed with grooves.
5. A polishing tool according to claim 3 wherein an upper of said two layers includes beads of plastic, glass or a soluble material.
6. A polishing tool according to claim 1 wherein said polishing layers comprises hollow beads of plastic, glass or other soluble material.
7. An endless belt for polishing semiconductor wafers comprising a continuous unseamed textile fabric supporting a polishing layer, said polishing layer comprising a microcellular or microporous urethane.
8. An endless belt according to claim 7 wherein said fabric is woven and comprises aramid yarns oriented in the lengthwise direction.
9. An endless belt according to claim 8 wherein said polishing layer comprises two layers which are of different hardness.
10. An endless belt according to claim 7 wherein an exposed surface of said polishing layer is formed with grooves.
11. An endless belt according to claim 9 wherein an upper of said two layers includes beads of plastic, glass or a soluble material.
12. An endless belt according to claim 7 wherein said polishing layers comprises hollow beads of plastic, glass or other soluble material.
13. An endless belt for polishing optical flats comprising a continuous unseamed textile fabric supporting a polishing layer, said polishing layer comprising a microcellular or microporous urethane.
14. An endless belt according to claim 13 wherein said fabric is woven and comprises aramid yarns oriented in the lengthwise direction.

15. An endless belt according to claim 14 wherein said polishing layer comprises two layers which are of different hardness.
16. An endless belt according to claim 13 wherein an exposed surface of said polishing layer is formed with grooves.
17. An endless belt according to claim 15 wherein an upper of said two layers includes beads of plastic, glass or a soluble material.
18. An endless belt according to claim 13 wherein said polishing layers comprises hollow beads of plastic, glass or other soluble material.
19. An endless belt for polishing mirrors comprising a continuous unseamed textile fabric supporting a polishing layer, said polishing layer comprising a microcellular or microporous urethane.
20. An endless belt according to claim 20 wherein said fabric is woven and comprises aramid yarns oriented in the lengthwise direction.
21. An endless belt according to claim 20 wherein said polishing layer comprises two layers which are of different hardness.
22. An endless belt according to claim 19 wherein an exposed surface of said polishing layer is formed with grooves.
23. An endless belt according to claim 21 wherein an upper of said two layers includes beads of plastic, glass or a soluble material.
24. An endless belt according to Claim 19 wherein said polishing layers comprises hollow beads of plastic, glass or other soluble material.